Applicant: Lawrence D. Wong Attorney's Docket No.: 10559-586002 Intel Ref.: P12767C

Continuation Of

Serial No.: 10/161,104 : Herewith

Page : 3

AMENDMENTS TO THE CLAIMS:

This listing of claims replaces all prior versions and listings of claims in the application:

LISTING OF CLAIMS:

1 to 9. (Cancelled)

- 10. (Currently Amended) An integrated circuit, including A dielectric film comprising a carbon doped oxide (CDO) CDO film having a modulus of about 20 GPa or greater.
- 11. (Currently Amended) The integrated circuit dielectric of claim 10, wherein the CDO film has a dielectric constant of about 2 to about 4.
- 12. (Currently Amended) The integrated circuit dielectric of claim 10, wherein the CDO film has a dielectric constant less than about 3.
- 13. (Currently Amended) The integrated circuit dielectric of claim 10, wherein the CDO film has a density less than about 2 g/cm³.
- 14. (Currently Amended) The integrated circuit dielectric of claim 10, wherein the CDO film has a density of about 1.3 g/cm³ to about 1.4 g/cm³.

Applicant: Lawrence D. Wong Attorney's Docket No.: 10559-586002

Intel Ref.: P12767C

Continuation Of

Serial No.: 10/161,104 Filed: Herewith

Page: 4

15. (Currently Amended) The integrated-circuit dielectric of claim 11, wherein the dielectric comprises film is an interlevel dielectric film.

- 16. (Currently Amended) The integrated circuit dielectric of claim 10, wherein the CDO film has a modulus of about 20 GPa to about 25 GPa.
- 17. (Currently Amended) The integrated circuit dielectric of claim 16, wherein the dielectric has a dielectric constant is of about 2 to about 4.
- 18. (Currently Amended) The integrated circuit dielectric of claim 17, wherein the dielectric comprises film is an interlevel dielectric film.
- 19. (Currently Amended) An integrated circuit, including A dielectric film comprising a carbon doped oxide (CDO) CDO film having a hardness of about 2.8 GPa or greater to about 3.5 GPa.
- 20. (Currently Amended) The integrated circuit dielectric of claim 19, wherein the CDO film has a dielectric constant of about 2 to about 4.

Applicant: Lawrence D. Wong Attorney's Docket No.: 10559-586002 Intel Ref.: P12767C

Continuation Of

Serial No.: 10/161,104 : Herewith

: 5 Page

21. (Currently Amended) The integrated circuit dielectric of claim 20, wherein the dielectric comprises film is an interlevel dielectric film.

22. (Canceled)

- 23. (Currently Amended) The integrated circuit dielectric of claim 22 19, wherein the CDO film has a dielectric constant of about 2 to about 4.
- 24. (Currently Amended) The integrated circuit dielectric of claim 23, wherein the dielectric film is comprises an interlevel dielectric film.
- 25. (Currently Amended) An integrated circuit, including A dielectric film comprising a carbon doped oxide (CDO) CDO film having a hardness of about 2.8 GPa or greater and a modulus of about 20 GPa or greater.
- 26. (Currently Amended) The integrated circuit dielectric of claim 25, wherein the CDO film has a hardness of about 2.8 GPa to about 3.5 GPa and a modulus of about 20 GPa to about 25 GPa.
- 27. (Currently Amended) The integrated circuit dielectric of claim 26, wherein the CDO film has a dielectric constant of about 2 to about 4.

Applicant: Lawrence D. Wong Continuation Of Attorney's Docket No.: 10559-586002 Intel Ref.: P12767C

Serial No.: 10/161,104 : Herewith

Page : 6

28. (Currently Amended) The integrated circuit dielectric of claim 27, wherein the dielectric comprises film is an interlevel dielectric film.